



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Attorney Docket No.: LWM-A105

R/D

Inventor(s): Fan Zhong and Jonathan G. Bornstein

Serial No.: 09/874,434

Group Art Unit:

OC 1 1 2001

Filed: 06/04/01

Examiner:

TC 1700

Title: METHOD AND SYSTEM FOR A HIGH-DENSITY PLASMA DEPOSITION PROCESS FOR FABRICATING A TOP CLAD FOR PLANAR LIGHTWAVE CIRCUIT DEVICES

The Commissioner of Patents and Trademarks
Washington, D.C. 20231

Sir:

Information Disclosure Statement Submitted Pursuant to 37 C.F.R. 1.97(b)

The citations referenced herein, copies attached, may be material to the examination of the above-identified application and are, therefore, submitted in compliance with the duty of disclosure as defined in 37 C.F.R. 1.56. The Examiner is requested to make these citations of official record in the application.

This Information Disclosure Statement submitted in accordance with 37 C.F.R. 1.97(b) is not to be construed as a representation that a search has been made, that additional items material to the examination of this application do not exist, or that any one or more of these citations constitute prior art under 35 U.S.C. 102.

The Examiner's attention is respectfully directed to the following U.S. Patents:

Pat. No.	Pat. Title	Grant Date
5,904,491	PLANAR WAVEGUIDES	05/18/99
5,991,487	SILICON-BASED SEMICONDUCTOR PHOTODETECTOR WITH AN IMPROVED THIN OPTICAL WAVEGUIDE LAYER	11/23/99
6,108,480	OPTICAL DEVICE WITH A GROOVE ACCURATELY FORMED	08/22/00
5,978,539	OPTICAL DEVICE HAVING A TEMPERATURE INDEPENDENT SPECTRAL RESPONSE USING NONPLANAR GEOMETRIC DISTORTION OF A SUBSTRATE	11/02/99
6,002,823	TUNABLE DIRECTIONAL OPTICAL WAVEGUIDE COUPLERS	12/14/99
5,500,916	METHOD FOR MAKING BRAGG REFLECTORS FOR WAVEGUIDES	03/19/96
4,851,025	PROCESS FOR PRODUCING A PLANAR OPTICAL WAVEGUIDE	07/25/89
4,934,774	OPTICAL WAVEGUIDE AND METHOD FOR ITS MANUFACTURE	06/19/90
5,408,569	OPTICAL CHANNEL WAVEGUIDE HAVING A HIGH GERMANIA CLADDING	04/18/95
	CONTENT	
4,045,198	METHOD OF PREPARING A FOREPRODUCT FOR THE PRODUCTION OF AN OPTICAL LIGHTCONDUCTOR	08/30/77
4,242,118	OPTICAL FIBER MANUFACTURE	12/30/80

Please direct all correspondence concerning the above-identified application to the following address:

WAGNER, MURABITO & HAO LLP
Two North Market Street, Third Floor
San Jose, California 95113
(408) 938-9060

Respectfully submitted,

Date:

07/24/01

By:

Glenn D. Barnes
Reg. No. 42,293



1731

Patent

Docket No.: LWM-A105

Information Disclosure Statement Transmittal

I hereby certify that this transmittal of the below described document is being deposited with the United States Postal Service in an envelope bearing First Class Postage and addressed to the Commissioner of Patents and Trademarks, Washington, D.C., 20231, on the below date of deposit.			
Date of Deposit:	10/04/01	Name of Person Making the Deposit:	Julie Gibson
		Signature of the Person Making the Deposit:	<i>Julie Gibson</i>

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OCT 11 2001
TC 1700

The Commissioner of Patents and Trademarks
Washington, D.C. 20231

Sir:

Information Disclosure Statement Transmittal

Transmitted herewith is the following:

- Formal drawings, totaling sheets.
- Informal drawings, totaling sheets.
- Certification for PTO Consideration
- ☒ Information Disclosure statement (1 sheets)
- Information Disclosure statement and late filing fee
- ☒ Form 1449
- Petition for Extension of Time
- ☒ Other: References

Fee Calculation (for other than a small entity)

Fee Items	Fee Rate	Total
Petition for Extension of Time (fee calculated elsewhere)	\$.00	
Information Disclosure Statement, late filing	\$240.00	
Other:		
Total Fees		

PAYMENT OF FEES

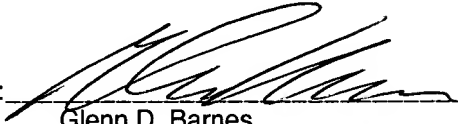
1. The full fee due in connection with this communication is provided as follows:
 - ☒ The Commissioner is hereby authorized to charge any additional fees associated with this communication or credit any overpayment to Deposit Account No.: 23-0085.
A duplicate copy of this authorization is enclosed.
 - ☐ A check in the amount of \$
 - ☐ Charge any fees required or credit any overpayments associated with this filing to Deposit Account No.: 23-0085.

Please direct all correspondence concerning the above-identified application to the following address:

WAGNER, MURABITO & HAO LLP
Two North Market Street, Third Floor
San Jose, California 95113
(408) 938-9060

Respectfully submitted,

Date: 10/4/01

By: 
Glenn D. Barnes
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OCT 11 2001

TC 1700Form 1449**U.S. Patent Documents**

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	A	5,904,491	05/18/99	Ojha	438	31	04/23/97
	B	5,991,487	11/23/99	Sugiyama	385	129	09/22/97
	C	6,108,480	08/22/00	Mizuta	385	129	07/28/99
	D	5,978,539	11/02/99	Davies	385	129	10/03/97
	E	6,002,823	12/14/99	Chandross	385	50	08/05/98
	F	5,500,916	03/19/96	Cirelli	385	37	09/09/94
	G	4,851,025	07/25/89	Siefert	65	31	12/02/87
	H	4,934,774	06/19/90	Kalnitsky	350	96.12	06/08/89
	I	5,408,569	04/18/95	Nishimoto	385	132	03/21/94
	J	4,045,198	08/30/77	Rau	65	33	08/24/76
	K	4,242,118	12/30/80	Irven	65	3	04/27/79

Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
	L							
	M							
	N							
	O							
	P							
	Q							

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	R	
	S	
	T	
Examiner		Date Considered

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered.
Include copy of this form with next communication to applicant.